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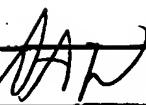
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Complete if Known	
Application Number	10/768,558
Filing Date	January-29, 2004
First Named Inventor	Christopher Hamlin
Group Art Unit	2825
Examiner Name	S. Whitmore
Attorney Docket No.	/03-2089

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	U.S. Patent Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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Examiner signature		Date considered	8/3/05
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1/29/04

In Place of FORM PTO-1449 (Modified)

Serial No.:

Applicant: Christopher Hamlin, et al.

Filing Date: January 29, 2004

Group:

Atty. Docket No.: 03-2099

EXAMINER NAME: S. Whitmore

**LIST OF PATENTS AND PUBLICATIONS FOR
APPLICANT'S INFORMATION DISCLOSURE
STATEMENT**

Reference Designation

U.S. PATENT DOCUMENTS**FOREIGN PATENT DOCUMENTS****OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

Examiner

Initial

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Examiner:

Date Considered:

8/3/05

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